

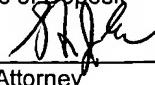


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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of:

Applicant : Shuwen Guo
Appln. No. : 10/658,042
Filed : September 9, 2003
Title : METHOD FOR MAKING AN INFRARED DETECTOR
AND INFRARED DETECTOR
Docket No. : 015559-282
Art Unit : 2878

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Pursuant to 37 C.F.R. §1.56, the Examiner's attention is directed to the references listed on the attached Information Disclosure Citation. Copies of all foreign patent documents and non-patent literature references are provided herewith.

It is to be understood that the present submission of art is in no way intended to be a waiver of any arguments or defenses available to the applicant under the rules of the U.S. Patent and Trademark Office and the statutes of the United States.

No fee is required. The Commissioner is authorized to charge any additional fees required by this paper or to credit any overpayment to Deposit Account No. 20-0809.

Respectfully submitted:

By: 

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INFORMATION DISCLOSURE CITATION

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U.S. PATENT DOCUMENTS

Examiner	Document No.	Date	Name	Class	Sub	
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Examiner	Document No.	Date	Country	Class	Sub	Y	N
	1072875	01/2001	Europe			X	

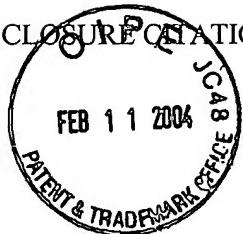
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Hsieh, Ming-Chin et al., "Design and Fabrication of a Novel Crystal SiGeC Far Infrared Sensor with Wavelength 8-14 Micrometer," <u>IEEE Sensors Journal</u> , Vol. 2, No. 4, pp. 360-365 (08/2002)
Taniguchi, Y. et al., "Pyroelectric Infrared Sensor Using PZT Thin Plate on Diaphragm as Sensitive Elements," <u>Electronics and Communications in Japan, Part 2</u> , Vol. 79, No. 7, pp. 86-96 (01/1996)
Sánchez, S. et al., "A High T _C Superconductor Bolometer on a Silicon Nitride Membrane," <u>Journal of Microelectrochemical Systems</u> , Vol. 7, No. 1, pp. 62-67 (03/1998)

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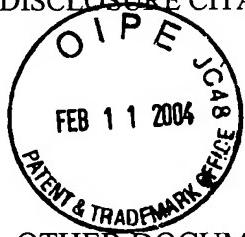
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	Web page relating to "CYCLOTENE Dry-Etch Resins," by The Dow Chemical Company (date of first publication unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.
	Web page relating to "CYCLOTENE Planarization," by The Dow Chemical Company (date of first publication unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.
	Web page relating to "CYCLOTENE Plasma Etching," by The Dow Chemical Company (date of first publication unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.

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